

ABSTRACT OF THE DISCLOSURE

A doping device of the present invention has a vacuum container defining a chamber therein. The container has a portion made of dielectric material and bearing an impurity to be doped in a substrate provided in the chamber. Also provided is a plasma source for generating a plasma in the chamber by forming an electric field through the portion of the container. With the device, ion in the plasma impinges against the portion of the container, feeding the impurity out of the portion of the container into the chamber.